

## Effect of silicon doping on low temperature magnetic interactions in epitaxial films of $\text{Mn}_5(\text{Ge}_{1-x}\text{Si}_x)_3$ : zero-field $^{55}\text{Mn}$ NMR study

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$\text{Mn}_5\text{Ge}_3$  and  $\text{Mn}_5\text{Si}_3$  are two isostructural compounds crystallizing in the hexagonal  $\text{D}_{8h}$  structure (space-group  $\text{P6}_3/\text{mcm}$ ) that can be mutually alloyed over the entire concentration range. The two end compositions of the  $\text{Mn}_5(\text{Ge}_{1-x}\text{Si}_x)_3$  series exhibit very different magnetic behavior:  $\text{Mn}_5\text{Ge}_3$  is a metallic ferromagnet with a Curie temperature of 296 K whereas  $\text{Mn}_5\text{Si}_3$  reveals a complex antiferromagnetic order at low temperatures: a chiral spin structure below 65 K and a collinear spin arrangement between 65 K and 100 K. Their unit cell contains two formula units, with the manganese atoms in two Wyckoff crystallographic positions: 4(*d*) and 6(*g*) (here denoted as  $\text{Mn}_\text{I}$  and  $\text{Mn}_\text{II}$  sites, respectively). It was shown that the  $\text{Mn}_5(\text{Ge}_{1-x}\text{Si}_x)_3$  films can be grown epitaxially on Ge(111) substrates. With the aim to understand local magnetic properties in each of the two manganese sites as a function of Si content we have undertaken a zero-field  $^{55}\text{Mn}$  NMR study in a series of the  $\text{Mn}_5(\text{Ge}_{1-x}\text{Si}_x)_3$  epitaxial films with silicon concentration ( $0 \leq x \leq 0.5$ ).

$^{55}\text{Mn}$  NMR experiment probes the local hyperfine field: in the pristine  $\text{Mn}_5\text{Ge}_3$  compound at 4.2 K the manganese atoms located at the 4(*d*) positions give the resonance signal at 207 MHz (central frequency of the quadrupolar structure) corresponding to the local hyperfine field of 19,6 T, whereas those in the 6(*g*) sites experience hyperfine field of 40,8 T (resonance frequency 430 MHz).

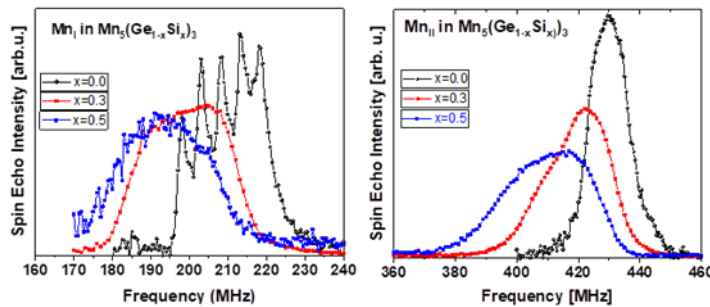


Fig.1  $^{55}\text{Mn}$  NMR spectra recorded at 4.2 K from the  $\text{Mn}_5(\text{Ge}_{1-x}\text{Si}_x)_3$  epitaxial films (60 nm thick) as a function of silicon content  
a)  $\text{Mn}_\text{I}$  environments  
b)  $\text{Mn}_\text{II}$  environments.

Upon silicon substitution two effects are readily visible (Fig 1): i) the NMR spectra shift towards lower frequencies evidencing the drop of the average hyperfine field on both manganese sites and ii) the NMR spectrum from the  $\text{Mn}_\text{II}$  sites develops a broad low frequency profile revealing the presence of a  $\text{Mn}_\text{II}$  population with the reduced magnetic moment. The thorough analysis of NMR data shows that substitution of Ge atoms by Si significantly modifies the exchange interactions involving the 6(*g*) manganese sites, leading to a drop of the magnetic moment of those  $\text{Mn}_\text{II}$  atoms that have Si neighbour instead of Ge. The effect on the  $\text{Mn}_\text{I}$  sites is secondary and consists in a smaller contribution of the transferred hyperfine field due to the reduced magnetic moment of the  $\text{Mn}_\text{II}$  neighbors and a loss of the quadrupolar structure due to the inhomogeneity brought by Ge/Si replacement.